L Number	Hits	Search Text	DB	Time stamp
1	22	(deflect\$ with (light or radiation) with cantilever)	USPAT;	2004/02/11
		and (silicon with (mirror or reflector))	US-PGPUB;	09:15
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
2	38	(deflect\$ with (light or radiation) with cantilever)	USPAT;	2004/02/11
		and (silicon with etch\$) and (mirror or reflector or	US-PGPUB;	09:18
		micromirror or micro?mirror)	EPO; JPO;	
			DERWENT;	
			IBW_TDB	
3	152	(deflect\$ with (light or radiation)) and cantilever\$	USPAT;	2004/02/11
		and (silicon with etch\$) and (mirror or reflector or	US-PGPUB;	09:28
		micromirror or micro?mirror)	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
4	7	("4182544"   "4657339"   "4669817"   "4674828"	USPAT	2004/02/11
		"4675521"   "4684208"   "4705349").PN.		09:22
5	2	("4182544").PN.	USPAT;	2004/02/11
			US-PGPUB;	09:27
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
6	457	(deflect\$ with (light or radiation)) and fix\$3 and	USPAT;	2004/02/11
		(silicon with etch\$) and (mirror or reflector or	US-PGPUB;	09:28
		micromirror or micro?mirror)	EPO; JPO;	
		·	DERWENT;	
	•		IBM_TDB	
7	403	(reflect\$ with (light or radiation)) and cantilever\$	USPAT;	2004/02/11
		and (silicon with etch\$) and (mirror or reflector or	US-PGPUB;	09:43
		micromirror or micro?mirror)	EPO; JPO;	
		·	DERWENT;	
			IBM_TDB	
8	113	((reflect\$ with (light or radiation)) and cantilever\$	USPAT;	2004/02/11
		and (silicon with etch\$) and (mirror or reflector or	US-PGPUB;	09:40
		micromirror or micro?mirror)) and anisotrop\$ and	EPO; JPO;	
		fiber	DERWENT;	
			IBM_TDB	
9	86	access\$ with internal\$ with position\$ with (plane or	USPAT;	2004/02/11
		mirror or reflector or deflector)	US-PGPUB;	09:41
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
10	77	((reflect\$ or deflect\$) with (light or radiation)) and	USPAT;	2004/02/11
1		(intersect\$ with (passage or channel))and (silicon	US-PGPUB;	09:44
		with etch\$) and (mirror or reflector or micromirror	EPO; JPO;	
		or micro?mirror)	DERWENT;	
			IBM_TDB	
-	2	("6008128").PN.	USPAT;	2002/09/17
			US-PGPUB;	09:09
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	

	576	(359/223).CCLS.	USPAT;	2003/03/07
	576	(337/223),0023.	US-PGPUB;	17:14
			EPO; JPO;	17.17
			DERWENT;	
			IBM_TDB	
	255	(250/200) (7) 6	USPAT;	2002/02/07
_	255	(359/298). <i>CC</i> LS.		2003/03/07
			US-PGPUB;	17:14
			EPO; JPO;	
			DERWENT;	
	505	(250,020) (6) 6	IBM_TDB	2002/02/07
-	505	(359/838). <i>CC</i> LS.	USPAT;	2003/03/07
			US-PGPUB;	17:14
			EPO; JPO;	
			DERWENT;	
		(005.444) 661.6	IBM_TDB	2002 (02 (07
-	88	(205/116). <i>CC</i> LS.	USPAT;	2003/03/07
			US-PGPUB;	17:15
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	135	((359/223).CCLS.) and silicon\$	USPAT;	2002/09/17
			US-PGPUB;	09:20
			EPO; JPO;	
			DERWENT;	
			IBW_TDB	
-	85	((359/298).CCLS.) and silicon\$	USPAT;	2002/09/17
			US-PGPUB;	10:21
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	66	((359/838).CCLS.) and silicon\$	USPAT;	2002/09/17
,			US-PGPUB;	10:30
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	8	((205/116).CCLS.) and silicon\$	USPAT;	2002/09/17
			US-PGPUB;	10:33
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	421	silicon and mirror and bulk and monolith\$ and	USPAT;	2002/09/17
		crystal\$4	US-PGPUB;	10:43
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	46	(silicon and mirror and bulk and monolith\$ and	USPAT;	2002/09/17
		crystal\$4) and inlet and outlet	US-PGPUB;	10:37
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	

	31	silicon and mirror and bulk and monolith\$ and	USPAT;	2002/09/17
		(crystal\$4 adj plane)	US-PGPUB;	10:51
		(crystaly rad) plane)	EPO; JPO;	10.31
			DERWENT;	
			IBM_TDB	
	89	(divole adi america adi dilipan) and minnon and	USPAT;	2003/07/30
-	09	(single adj crystal adj silicon) and mirror and	US-PGPUB;	08:28
		(crystal\$4 adj plane)	EPO; JPO;	00.20
			DERWENT;	
	100		IBM_TDB	2002/00/17
-	692	(single adj crystal adj silicon) and mirror and plane	USPAT;	2002/09/17
		and etch\$3	US-PGPUB;	11:43
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	309	((single adj crystal adj silicon) and mirror and plane	USPAT;	2002/09/17
		and etch\$3) and anisotrop\$	US-PGPUB;	11:09
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	. 101	(((single adj crystal adj silicon) and mirror and plane	USPAT;	2002/09/17 11:10
		and etch\$3) and anisotrop\$) and fiber and optic\$4	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	121	(single and crystal and silicon) and mirror and plane	USPAT;	2002/09/17 14:11
	1	and etch\$3 and anisotrop\$ and fiber and optic\$4 and	US-PGPUB;	
		internal\$2	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	256	single and crystal\$4 and silicon and mirror and	USPAT;	2002/09/17
		etch\$3 and stripe and intersect\$4	US-PGPUB;	14:25
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	118	(single and crystal\$4 and silicon and mirror and	USPAT;	2002/09/17
		etch\$3 and stripe and intersect\$4) and internal	US-PGPUB;	11:58
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	373	(single near crystal\$4 near silicon) with mirror	USPAT;	2002/09/17
			US-PGPUB;	12:05
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	39	((single near crystal\$4 near silicon) with mirror) and	USPAT;	2002/09/17
		(fiber near optic\$4)	US-PGPUB;	12:06
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	

	3645	digital and mirror and device and silicon and	USPAT;	2002/09/17
	30.10	crystal\$4	US-PGPUB;	14:12
			EPO; JPO;	• · · •
			DERWENT;	
			IBM_TDB	
<u>_</u>	168	(digital and mirror and device and silicon and	USPAT;	2002/09/17
	100	crystal\$4) and bulk and monolith\$	US-PGPUB;	14:12
		crystarpary and bark and monormap	EPO; JPO;	17.16
			DERWENT;	
			IBM_TDB	
	341	silicon and mirror and etch\$3 and stripe and	USPAT;	2002/09/17
	] 341	intersect\$4	US-PGPUB;	14:36
		mier seci p	EPO; JPO;	14.50
			DERWENT;	
			IBM_TDB	
	2259	silicon and mirror and pattern\$3 and anisotrop\$	USPAT;	2002/09/17
-	2239	silicon and mirror and parternos and anisotropo	US-PGPUB;	14:37
			EPO; JPO;	14.57
			DERWENT;	
			IBM_TDB	
	403	(single adj crystal\$4 adj silicon) and mirror and	USPAT;	2002/09/17
-	403	pattern\$3 and anisotrop\$	US-PGPUB;	15:20
		parternas and anisotropa	EPO; JPO;	15.20
			DERWENT;	
			IBM_TDB	
	o	(bulk with (single adj crystal\$4 adj silicon)) and	USPAT;	2002/09/17
_		(mirror near pattern\$3)	US-PGPUB;	15:22
		(mirror near parternas)	EPO; JPO;	13.22
			DERWENT;	
			IBM_TDB	
l _	20	silicon and (mirror near pattern\$3) and (anisotrop\$	USPAT;	2002/09/17
		near etch\$3)	US-PGPUB;	15:34
		nodi orongo)	EPO; JPO;	10.01
			DERWENT;	
			IBM_TDB	
-	16	silicon and ((mirror near pattern\$3) with array\$)	USPAT;	2002/09/17
		Comment of the part of the par	US-PGPUB;	15:39
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	2585	(mirror with array\$) and silicon	USPAT;	2002/09/17
		,,,	US-PGPUB;	16:16
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	9	(mirror with array\$) and (bulk with single with	USPAT;	2002/09/17
		crystal\$4 with silicon)	US-PGPUB;	15:43
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	

-	2	((mirror with array\$) and silicon ) and anisotrop\$ and	USPAT;	2002/09/17
		(bulk near crystal\$4)	US-PGPUB;	15:44
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
_	2	monolithic adj bulk adj crystal adj silicon	USPAT;	2002/09/17
		monomino day bank day or your day of moon	US-PGPUB;	16:17
			EPO; JPO;	10.07
			DERWENT;	
			IBM_TDB	
	2	monolithic with bulk with crystal with silicon	USPAT;	2002/09/17
-	2	monolithic with bulk with crystal with silicon	US-PGPUB;	16:17
			1	10.17
			EPO; JPO;	
			DERWENT;	
		1000	IBM_TDB	2000 100 117
-	1586	monolithic and bulk and crystal and silicon	USPAT;	2002/09/17
			US-PGPUB;	16:18
			EPO; JPO;	
			DERWENT;	
			IBW_TDB	
-	25	(monolithic and bulk and crystal and silicon) and	USPAT;	2002/09/17
		(crystalline near plane)	US-PGPUB;	16:19
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	362	(monolithic and bulk and crystal and silicon) and	USPAT;	2002/09/17
		(crystalline and plane)	US-PGPUB;	16:20
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
_	4	((monolithic and bulk and crystal and silicon) and	USPAT;	2002/09/17
		(crystalline and plane)) and (micro?mirror or (micro	US-PGPUB;	16:20
		adj mirror))	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
_	109	((monolithic and bulk and crystal and silicon) and	USPAT;	2002/09/17
		(crystalline and plane)) and mirror	US-PGPUB;	16:41
		(or you and plane)) and mirror	EPO; JPO;	
			DERWENT;	
	]		IBM_TDB	
		cilican noon minnan room array	USPAT;	2002/09/17
-	4	silicon near mirror near array		
			US-PGPUB;	16:42
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	1415	digital near (micromirror or micro?mirror or (micro	USPAT;	2002/09/17
		adj mirror)) near device	US-PGPUB;	16:43
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	

	350	(4) -14-1 (-1)	USPAT;	2002/09/17
-	350	(digital near (micromirror or micro?mirror or (micro	US-PGPUB;	17:12
		adj mirror)) near device) and silicon	· ·	17.12
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	0000/00/47
-	16	(digital near (micromirror or micro?mirror or (micro	USPAT;	2002/09/17
		adj mirror)) near device) and (single adj crystal adj	US-PGPUB;	17:14
		silicon)	EPO; JPO;	
,			DERWENT;	
			IBM_TDB	
-	3991	(mirror or reflect\$) and (single adj crystal adj	USPAT;	2002/09/17
		silicon)	US-PGPUB;	17:16
,			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	240	((mirror or reflect\$) and (single adj crystal adj	USPAT;	2002/09/17
		silicon)) and bulk and monolith\$	US-PGPUB;	17:42
			EPO; JPO;	
			DERWENT;	
	]		IBW_TDB	
<b>-</b> . !	148	anisotrop\$ with silicon with array with etch\$4	USPAT;	2002/09/17
	;		US-PGPUB;	17:43
			EPO; JPO;	
	[		DERWENT;	
			IBM_TDB	
-	226	(anisotrop\$ with silicon with process\$) and (mirror or	USPAT;	2002/09/17
		reflector)	US-PGPUB;	18:38
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	25	silicon and mirror and passage and (crystalline adj	USPAT;	2002/09/17
		plane)	US-PGPUB;	18:42
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	42	(monolithic and bulk and crystal and silicon) and	USPAT;	2002/09/17
		(mirror or reflector) and crystalline and plane and	US-PGPUB;	18:44
		intersect\$4	EPO; JPO;	
			DERWENT;	
,			IBM_TDB	
_	606	(359/223).CCLS.	USPAT;	2003/07/30
			US-PGPUB;	08:10
,			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
_	290	(359/298). <i>CC</i> LS.	USPAT;	2003/07/30
		\ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \	US-PGPUB;	08:10
			EPO; JPO;	
			DERWENT;	
			IBW_TDB	

	553	(359/838).CCLS.	USPAT;	2003/07/30
_	553	(3377636).cct3.	US-PGPUB;	08:10
			EPO; JPO;	00.10
			DERWENT;	
			IBM_TDB	
		(205 444) CCI C	USPAT;	2002/07/20
_	88	(205/116). <i>CC</i> LS.		2003/07/30
			US-PGPUB;	08:10
			EPO; JPO;	
			DERWENT;	
		((0.50 (0.00) 4.51 a.)	IBM_TDB	2002/02/07
-	42	((359/223).CCLS.) and (mirror or reflector) and	USPAT;	2003/03/07
		anisotrop\$	US-PGPUB;	17:28
			EPO; JPO;	
			DERWENT;	
			IBW_TDB	
-	23	((359/298).CCLS.) and (mirror or reflector) and	USPAT;	2003/03/07
		anisotrop\$	US-PGPUB;	17:52
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	15	((359/838).CCLS.) and (mirror or reflector) and	USPAT;	2003/03/07
1	!	anisotrop\$	US-PGPUB;	17:54
			EPO; JPO;	
			DERWENT;	
			IBW_TDB	
-	1	((205/116).CCLS.) and (mirror or reflector) and	USPAT;	2003/03/07
		anisotrop\$	US-PGPUB;	17:56
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
_	244	silicon and ((mirror or reflector) with anisotrop\$)	USPAT;	2003/03/10
			US-PGPUB;	08:20
			EPO; JPO;	
			DERWENT;	
		•	IBM_TDB	
-	2	westra.in. and silicon and anisotrop\$	USPAT;	2003/03/10
		·	US-PGPUB;	08:21
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	101	westra.in.	USPAT;	2003/03/10
			US-PGPUB;	08:21
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	422	((bulk or (single near3 crystal\$) or homogen\$) near3	USPAT;	2003/07/30
		silicon) and (internal with (mirror or reflect\$))	US-PGPUB;	09:34
		, , , , , , , , , , , , , , , , , , , ,	EPO; JPO;	
			DERWENT;	
			IBM_TDB	

_	71	(((bulk or (single near3 crystal\$) or homogen\$) near3	USPAT;	2003/07/30
-	,1	silicon) and (internal with (mirror or reflect\$))) and	US-PGPUB;	08:31
		anisotrop\$	EPO; JPO;	00.51
		anisotropa	DERWENT;	
	_	/// U / · I 2 1 145 1	IBM_TDB	2002/07/20
-	5	((bulk or (single near3 crystal\$) or homogen\$) near3	USPAT;	2003/07/30
		silicon) and (internal\$2 with (mirror or reflect\$) with	US-PGPUB;	09:02
		etch\$4)	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	1	((bulk or (single near3 crystal\$) or homogen\$) near3	USPAT;	2003/07/30
		silicon) and (atom\$6 with flat with (mirror or	US-PGPUB;	09:04
		reflect\$) with etch\$4)	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	6	((bulk or (single near3 crystal\$) or homogen\$) near3	USPAT;	2003/07/30
		silicon) and (atom\$6 with flat with (mirror or	US-PGPUB;	09:07
		reflect\$))	EPO; JPO;	
		•"	DERWENT;	
			IBM_TDB	
_	o	((bulk or (single near3 crystal\$) or homogen\$) near3	USPAT;	2003/07/30
		silicon) and (atom\$6 with flat with anisotrop\$)	US-PGPUB;	09:08
		Sincony and (arompo with that with ansorroppy)	EPO; JPO;	07.00
			DERWENT;	
			IBM_TDB	
	2	silicon same (atom\$6 with flat with anisotrop\$)	USPAT;	2003/07/30
-		silicon same (atompo with flat with anisotropy)	US-PGPUB;	09:10
				09.10
			EPO; JPO;	
			DERWENT;	
	_		IBM_TDB	0000 (07 (00
-	5	silicon same (atom\$6 with flat) same anisotrop\$	USPAT;	2003/07/30
			US-PGPUB;	09:10
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	512	((bulk or (single near3 crystal\$) or homogen\$) near3	USPAT;	2003/07/30
		silicon) and ((internal or bur\$3) with (mirror or	US-PGPUB;	09:13
		reflect\$))	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	356	(((bulk or (single near3 crystal\$) or homogen\$) near3	USPAT;	2003/07/30
		silicon) and ((internal or bur\$3) with (mirror or	US-PGPUB;	09:14
		reflect\$))) and etch\$4	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	69	(((bulk or (single near3 crystal\$) or homogen\$) near3	USPAT;	2003/07/30
		silicon) and ((internal or bur\$3) with (mirror or	US-PGPUB;	09:14
		reflect\$))) and (etch\$4 with plane)	EPO; JPO;	
			DERWENT;	
		•	IBM_TDB	
	1			1

-	166	((bulk or crystal\$ or homogen\$) near3 silicon) and	USPAT;	2003/07/30
		(internal with (mirror or reflect\$ or deflect\$)) and	US-PGPUB;	10:15
		anisotrop\$	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
_	324	((bulk or crystal\$ or homogen\$) near3 silicon) and	USPAT;	2003/07/30
		(integra\$ with (mirror or reflect\$ or deflect\$)) and	US-PGPUB;	11:13
		anisotrop\$	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
_	7	("4182544"   "4657339"   "4669817"   "4674828"	USPAT	2003/07/30
		"4675521"   "4684208"   "4705349").PN.		11:04
_	642	silicon and (integra\$ with (mirror or reflect\$ or	USPAT;	2003/07/30
_	042	deflect\$)) and (anisotrop\$ with etch\$3)	US-PGPUB;	11:16
		defiecty)) and (anisotropy with etchys)	EPO; JPO;	11.10
			DERWENT;	
	400	(intermed with (minute or well at the control of the state)	IBM_TDB	2002/07/20
-	182	(integra\$ with (mirror or reflect\$ or deflect\$)) and	USPAT;	2003/07/30
		(silicon with anisotrop\$ with etch\$3) and (hole or	US-PGPUB;	11:56
		bore or passage)	EPO; JPO;	
			DERWENT;	
			IBW_TDB	
-	84	(silicon with (mirror or reflect\$ or deflect\$) with	USPAT;	2003/07/30
		(micromachin\$ or micro?machin\$)) and (anisotrop\$	US-PGPUB;	11:58
		with etch\$3)	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	35	(atom\$6 near3 (smooth\$4 or flat\$4)) with etch\$4	USPAT;	2003/07/30
		with silicon	US-PGPUB;	12:25
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	256	(atom\$6 near3 (smooth\$4 or flat\$4)) and (mirror or	USPAT;	2003/07/30
i	!	reflect\$ or deflect\$) and etch\$4 and silicon	US-PGPUB;	12:26
		, , , ,	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
_	35	((atom\$6 near3 (smooth\$4 or flat\$4)) same (mirror	USPAT;	2003/07/30
		or reflect\$ or deflect\$)) and etch\$4 and silicon	US-PGPUB;	12:31
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
_	52	(atom\$6 near3 (smooth\$4 or flat\$4)) and (mirror or	USPAT;	2003/07/30
		reflect\$ or deflect\$) and (anisotrop\$ with etch\$4)	US-PGPUB;	12:32
		and silicon	EPO; JPO;	16.06
		and sincon	DERWENT;	
	] .		IBM_TDB	
_	678	(350/223) CCI S	1 —	2004/02/10
-	6/6	(359/223). <i>CC</i> LS.	USPAT;	2004/02/10
			US-PGPUB;	10:52
			EPO; JPO;	
			DERWENT;	
	<u> </u>		IBM_TDB	

				T
-	339	(359/298).CCLS.	USPAT;	2004/02/10
			US-PGPUB;	10:53
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	603	(359/838). <i>CC</i> LS.	USPAT;	2004/02/10
			US-PGPUB;	10:53
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
_	89	(205/116).CCLS.	USPAT;	2004/02/10
			US-PGPUB;	10:53
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
_	1340	(mirror or reflect\$ or deflect\$ or micromirror or	USPAT;	2004/02/10
	1540	(micro?mirror)) with internal\$ with (fixed or	US-PGPUB;	13:13
		stationary)	EPO; JPO;	
		Stationary)	DERWENT;	
			IBM_TDB	
	4	//wiwww.au.uaflaata.au.daflaata.au.wianawinnan.an	USPAT;	2004/02/10
-	4	((mirror or reflect\$ or deflect\$ or micromirror or	US-PGPUB;	13:54
		(micro?mirror)) with internal\$ with (fixed or		13.54
		stationary)) and (anisotrop\$ with etch\$) and ((bulk	EPO; JPO;	
		or (single with crystal\$)) with silicon)	DERWENT;	
	1212		IBM_TDB	2004/02/10
-	1340	(mirror or reflect\$ or deflect\$ or micromirror or	USPAT;	2004/02/10
		(micro?mirror) or micro adj mirror) with internal\$	US-PGPUB;	13:16
	]	with (fixed or stationary)	EPO; JPO;	
	!		DERWENT;	
	†		IBM_TDB	
-	0	(mirror or reflect\$ or deflect\$ or micromirror or	USPAT;	2004/02/10
		(micro?mirror) or micro adj mirror) with internal\$	US-PGPUB;	13:16
		with (expos\$ with durface)	EPO; JPO;	
			DERWENT;	
	!		IBW_TDB	
-	421	(mirror or reflect\$ or deflect\$ or micromirror or	USPAT;	2004/02/10
		(micro?mirror) or micro adj mirror) with internal\$	US-PGPUB;	13:16
		with (expos\$ with surface)	EPO; JPO;	
	]		DERWENT;	
			IBW_TDB	
-	149	((mirror or reflect\$ or deflect\$ or micromirror or	USPAT;	2004/02/10
		(micro?mirror) or micro adj mirror) with internal\$	US-PGPUB;	15:43
1		with (expos\$ with surface)) and (inlet or passage or	EPO; JPO;	
		outlet)	DERWENT;	
			IBM_TDB	
-	544	((bulk or (single with crystal\$) or monolith\$) with	USPAT;	2004/02/10
1	1	silicon) same (crystal\$ with (mirror or reflect\$) with	US-PGPUB;	14:34
	1	surface)	EPO; JPO;	
			DERWENT;	
			IBM_TDB	

-	88	(((bulk or (single with crystal\$) or monolith\$) with	USPAT;	2004/02/10
		silicon) same (crystal\$ with (mirror or reflect\$) with	US-PGPUB;	14:35
		surface)) and (anisotrop\$ near3 etch\$)	EPO; JPO;	
			DERWENT;	
			IBM TDB	
_	7	(((bulk or (single with crystal\$) or monolith\$) with	USPAT;	2004/02/10
	<b>'</b>	silicon) same (crystal\$ with (mirror or reflect\$) with	US-PGPUB;	14:36
		surface)) and (total\$ with internal\$ with reflect\$)	EPO; JPO;	11.00
		Surface), and (rotally with internally with rotteerly)	DERWENT;	
			IBM_TDB	
	1094	((bulk or (single with crystal\$) or monolith\$) with	USPAT;	2004/02/10
_	1074	silicon) same ((mirror or reflect\$ or deflect\$) with	US-PGPUB;	15:00
		surface)	EPO; JPO;	15.00
		Surface)	DERWENT;	
			1	
	204	الذي الأعلى من المناطقة المناط	IBM_TDB	2004/02/10
-	204	(((bulk or (single with crystal\$) or monolith\$) with	USPAT;	2004/02/10
		silicon) same ((mirror or reflect\$ or deflect\$) with	US-PGPUB;	14:36
		surface)) and ((anisotrop\$ near3 etch\$) or (deep\$3	EPO; JPO;	
		with reactive\$2 with etch\$))	DERWENT;	
			IBM_TDB	
-	11	((((bulk or (single with crystal\$) or monolith\$) with	USPAT;	2004/02/10
		silicon) same ((mirror or reflect\$ or deflect\$) with	US-PGPUB;	15:43
		surface)) and ((anisotrop\$ near3 etch\$) or	EPO; JPO;	
		(reactive\$2 with ion with etch\$))) and (total\$ with	DERWENT;	
		internal\$ with reflect\$)	IBW_TDB	
-	253	(((bulk or (single with crystal\$) or monolith\$) with	USPAT;	2004/02/10
		silicon) same ((mirror or reflect\$ or deflect\$) with	US-PGPUB;	15:12
		surface)) and ((anisotrop\$ near3 etch\$) or	EPO; JPO;	
		(reactive\$2 with ion with etch\$))	DERWENT;	
			IBM_TDB	
-	8	(("5600741") or ("5487124") or ("5485538") or	USPAT;	2004/02/10
		("5757994")).PN.	US-PGPUB;	15:03
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
<b>-</b>	35	((bulk or (single with crystal\$) or monolith\$) with	USPAT;	2004/02/10 15:11
		silicon) same ((mirror or reflect\$ or deflect\$) with	US-PGPUB;	
		surface with (internal\$ or cavity))	EPO; JPO;	1
		·	DERWENT;	
			IBM_TDB	
-	468	((bulk or (single with crystal\$) or monolith\$) with	USPAT;	2004/02/10
		silicon) and (((mirror or reflect\$ or deflect\$) with	US-PGPUB;	15:36
		surface) with (internal\$ or cavity))	EPO; JPO;	
		, , , , , , , , , , , , , , , , , , , ,	DERWENT;	
			IBM_TDB	
	149	(((bulk or (single with crystal\$) or monolith\$) with	USPAT;	2004/02/10
		silicon) and (((mirror or reflect\$ or deflect\$) with	US-PGPUB;	16:23
		surface) with (internal\$ or cavity))) and ((anisotrop\$	EPO; JPO;	
		near3 etch\$) or (reactive\$2 with ion with etch\$))	DERWENT;	
			IBM_TDB	

-	47	((bulk or (single with crystal\$) or monolith\$) with	USPAT;	2004/02/10
		silicon) and (((mirror or reflect\$ or deflect\$) with	US-PGPUB;	15:38
		surface) with (internal\$ or cavity)) and (guid\$ with	EPO; JPO;	
		light)	DERWENT;	
		,	IBM_TDB	
_	7242	((mirror or reflect\$ or deflect\$) with surface with	USPAT;	2004/02/10
-	/ 272	silicon)	US-PGPUB;	15:41
		Silicony	EPO; JPO;	15.41
			DERWENT;	
	1112	///	IBM_TDB	2004/02/10
-	1112	(((mirror or reflect\$ or deflect\$) with surface with	USPAT;	2004/02/10
		silicon)) and ((anisotrop\$ near3 etch\$) or	US-PGPUB;	16:56
		(reactive\$2 with ion with etch\$))	EPO; JPO;	
			DERWENT;	
			IBW_TDB	
-	1118	((mirror or reflect\$ or deflect\$ or micromirror or	USPAT;	2004/02/10
		(micro?mirror) or micro adj mirror) with surface with	US-PGPUB;	15:51
		silicon) and ((anisotrop\$ near3 etch\$) or (reactive\$2	EPO; JPO;	
		with ion with etch\$))	DERWENT;	
			IBM_TDB	
-	28	(((mirror or reflect\$ or deflect\$ or micromirror or	USPAT;	2004/02/10
		(micro?mirror) or micro adj mirror) with surface with	US-PGPUB;	15:44
		silicon) and ((anisotrop\$ near3 etch\$) or (reactive\$2	EPO; JPO;	
		with ion with etch\$))) and (total\$ with internal\$ with	DERWENT;	
		reflect\$) and (optic\$4 with fiber)	IBM_TDB	
_	112	((mirror or reflect\$ or deflect\$ or micromirror or	USPAT;	2004/02/10
		(micro?mirror) or micro adj mirror) with cavity with	US-PGPUB;	16:21
		silicon) and ((anisotrop\$ near3 etch\$) or (reactive\$2	EPO; JPO;	
	1	with ion with etch\$))	DERWENT;	
		,	IBM_TDB	
_	185	(embed\$ or bur\$3) with (mirror or reflect\$ or	USPAT;	2004/02/10
	100	deflect\$ or micromirror or (micro?mirror) or micro	US-PGPUB;	16:22
		adj mirror) with silicon	EPO; JPO;	10.22
		daj mirror) with sincon	DERWENT;	
			IBM_TDB	
	185	(ambads on hunss) with (minner as self-ests es		2004/02/10
-	100	(embed\$ or bur\$3) with (mirror or reflect\$ or	USPAT;	16:55
		deflect\$ or micromirror or (micro?mirror) or (micro	US-PGPUB;	10:00
		adj mirror)) with silicon	EPO; JPO;	
			DERWENT;	
	1		IBM_TDB	2004/20/45
-	45	((embed\$ or bur\$3) with (mirror or reflect\$ or	USPAT;	2004/02/10
		deflect\$ or micromirror or (micro?mirror) or (micro	US-PGPUB;	16:23
		adj mirror)) with silicon) and ((anisotrop\$ near3	EPO; JPO;	
		etch\$) or (reactive\$2 with ion with etch\$))	DERWENT;	
			IBM_TDB	
-	175	(coupl\$ with (mirror or reflect\$ or deflect\$ or	USPAT;	2004/02/10
		micromirror or (micro?mirror) or (micro adj mirror))	US-PGPUB;	16:29
		with silicon) and (optic\$4 with fiber)	EPO; JPO;	
			DERWENT;	
			IBM_TDB	

-	7546	(mirror or reflect\$ or deflect\$ or micromirror or	USPAT;	2004/02/10
		(micro?mirror) or (micro adj mirror)) with silicon with	US-PGPUB;	16:56
		(plane or surface)	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	1163	((mirror or reflect\$ or deflect\$ or micromirror or	USPAT;	2004/02/10
		(micro?mirror) or (micro adj mirror)) with silicon with	US-PGPUB;	17:35
		(plane or surface)) and ((anisotrop\$ near3 etch\$) or	EPO; JPO;	
		(reactive\$2 with ion with etch\$))	DERWENT;	
			IBM_TDB	
-	680	(((mirror or reflect\$ or deflect\$ or micromirror or	USPAT;	2004/02/10
		(micro?mirror) or (micro adj mirror)) with silicon with	US-PGPUB;	16:58
		(plane or surface)) and ((anisotrop\$ near3 etch\$) or	EPO; JPO;	
		(reactive\$2 with ion with etch\$))) and (cavity or	DERWENT;	
		internal\$ or inside)	IBM_TDB	
-	270	((((mirror or reflect\$ or deflect\$ or micromirror or	USPAT;	2004/02/10
	.	(micro?mirror) or (micro adj mirror)) with silicon with	US-PGPUB;	16:58
		(plane or surface)) and ((anisotrop\$ near3 etch\$) or	EPO; JPO;	
		(reactive\$2 with ion with etch\$))) and (cavity or	DERWENT;	
		internal\$ or inside)) and (optic\$4 with fiber)	IBM_TDB	
-	143	(((((mirror or reflect\$ or deflect\$ or micromirror or	USPAT;	2004/02/10
		(micro?mirror) or (micro adj mirror)) with silicon with	US-PGPUB;	16:59
		(plane or surface)) and ((anisotrop\$ near3 etch\$) or	EPO; JPO;	
		(reactive\$2 with ion with etch\$))) and (cavity or	DERWENT;	
		internal\$ or inside)) and (optic\$4 with fiber)) and	IBM_TDB	
		switch\$ and coupl\$		
-	246	(anisotrop\$ with (reactive\$2 with ion with etch\$))	USPAT;	2004/02/10
		same groove	US-PGPUB;	17:47
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
<b>-</b> .	53	((anisotrop\$ with (reactive\$2 with ion with etch\$))	USPAT;	2004/02/10
		same groove) and ((bulk or (single with crystal\$) or	US-PGPUB;	17:39
		monolith\$) with silicon)	EPO; JPO;	
		, monotonity with state of	DERWENT;	·
			IBM_TDB	
_	14	((anisotrop\$ with (reactive\$2 with ion with etch\$))	USPAT;	2004/02/10
		same groove) and silicon and (optic\$4 with fiber)	US-PGPUB;	17:39
		Tame groote, and emedicated top news with tiber,	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	20	(anisotrop\$ with (reactive\$2 with ion with etch\$))	USPAT;	2004/02/10
		and v?groove and silicon and (optic\$4 with fiber)	US-PGPUB;	17:51
		יווים אין אוויים דיים אוויים וויים אוויים	EPO; JPO;	-7101
			DERWENT;	
			IBM_TDB	
_	105	anisotrop\$ and (reactive\$2 with ion with etch\$) and	USPAT;	2004/02/10
	103	v?groove and silicon and (optic\$4 with fiber)	US-PGPUB;	17:51
		T. g. ooto and sincon and (opincon with tibel)	EPO; JPO;	1,131
			DERWENT;	
			IBM_TDB	
	1		TOM_ 1 UD	l

-	195	(((mirror or reflect\$ or deflect\$ or micromirror or	USPAT;	2004/02/10
		(micro?mirror) or micro adj mirror) with surface with	US-PGPUB;	18:27
		silicon) and ((anisotrop\$ near3 etch\$) or (reactive\$2	EPO; JPO;	
		with ion with etch\$))) and (inlet or passage or outlet)	DERWENT;	
			IBM_TDB	